

# 选择性酸蚀技术用于断冠再接的研究

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**【摘要】目的** 探讨选择性酸蚀技术用于断冠再接的效果。**方法** 将50颗体外建立冠折模型的人下切牙随机分为5组,组1使用Easy One(EO)自酸蚀技术再接,组2使用EO选择性酸蚀技术再接,组3使用Clearfil S3 bond(CS3)自酸蚀技术再接,组4使用CS3选择性酸蚀技术再接,组5使用Single bond 2(SB2)全酸蚀技术再接。样本再接后测定剪切力或电镜观察,计算再接后强度恢复率。**结果** 组1与组2、组3与组4再接后强度恢复率无显著性差异( $P>0.05$ )。SB2用于断冠再接后的剪切力及强度恢复率均最低,组5显著低于组2( $P=0.043$ )及组3( $P=0.043$ )。电镜下,SB2的粘接界面与EO和CS3存在差异。**结论**选择性酸蚀技术的作用受粘接剂及粘接面状态影响,全酸蚀技术用于断冠再接没有优势。

**【关键词】** 断冠再接 自酸蚀 全酸蚀 选择性酸蚀

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## Effect of selective etching technique on tooth fragment reattachment

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**【Abstract】Objective** To discuss the effect of selective etching technique on tooth crown fragment reattachment. **Methods** 50 fractured human mandibular incisors were obtained and randomly assigned into 5 groups. G1: reattaching with Easy one (EO) following a self-etch approach, G2: selective enamel etching before application of EO, G3: reattaching with Clearfil S3 bond (CS3) following a self-etch approach, G4: selective enamel etching before application of CS3, G5: reattaching with Single bond 2 (SB2) following a total-etch approach. After reattaching, the fracture resistance was tested and the fracture morphology was observed using SEM. The recovery rate of fracture strength after reattachment (R) was also calculated. **Results** There was no significant difference in the R value between G1 and G2, G3 and G4 ( $P>0.05$ ). Both the fracture resistance and the recovery rate of SB2 had the lowest value. The R value of G5 was significantly lower than that of G2 ( $P=0.043$ ) and G3 ( $P=0.043$ ). SEM photomicrograph of the bonding interface showed different micromorphology between EO and CS3. **Conclusion** The effect of selective etching depended on both the adhesives and the condition of the fracture surface. Total-etch had no superiority on tooth fragment reattachment.

**【Key words】** Reattachment of tooth fragment Self-etch Total-etch Selective etching

断冠再接是自体牙原位修复牙体缺损的方法,

其临床应用得益于树脂粘接剂的发展<sup>[1]</sup>。自酸蚀树脂粘接剂能获得较高的牙本质粘接强度、术后敏感发生率低,但在釉质粘接强度及边缘封闭性方面不如全酸蚀技术。而选择性酸蚀技术(selective

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